

## PATENT ABSTRACTS OF JAPAN

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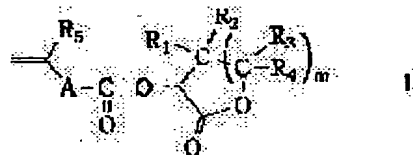
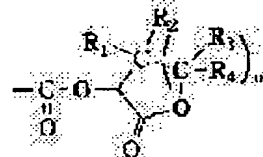
AOSO TOSHIKI

## (54) POSITIVE TYPE PHOTORESIST COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To improve adhesion to a substrate as well as to ensure satisfactory fitness for light in a short wavelength range, high sensitivity and superior resist pattern profile by incorporating a specified resin and a specified compd.

SOLUTION: This photoresist compsn. contains a resin having an ester group represented by formula I in each molecule and a compd. generating an acid when irradiated with active light or radiation. In formulae I, II each of R1-R4 may be same or different, is H or alkyl and (m) is 1 or 2. The resin is decomposed by the action of the acid to increase the solubility to an alkali soln. and contains repeating structural units corresponding to a monomer represented by formula II (where R5 is H or methyl and A is a single bond, alkylene, substd. alkylene, ether, thio-ether, carbonyl, ester, etc.).



## LEGAL STATUS

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